

AMENDMENT TRANSMITTAL LETTER (Large Entity)
 Applicant(s): Apostolos Voutsas

 Docket No.
 SLA0592

 Serial No
 09/893,866

 Filing Date
 June 28, 2001

 Examiner
 Asok K. Sarkar

 Group Art Unit
 2829

Invention: Method for Forming Silicon Films with Trace Impurities

FAX COPY RECEIVED**TO THE COMMISSIONER FOR PATENTS:****SEP 19 2002**

Transmitted herewith is an amendment in the above identified application.

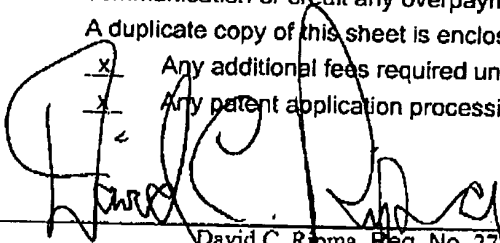
The fee has been calculated and is transmitted as shown below.

TECHNOLOGY CENTER 2800

CLAIMS AS AMENDED

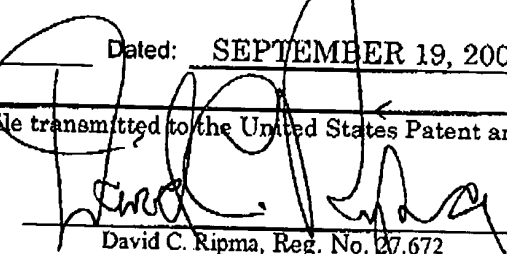
	CLAIMS REMAINING AFTER AMENDMENT	HIGHEST # PREV. PAID FOR	NUMBER OF EXTRA CLAIMS PRESENT	RATE	ADDITIONAL FEE
TOTAL CLAIMS	25 -	23 =	2	x \$18.00	\$36.00
INDEP. CLAIMS	3 -	3 =	0	x \$84.00	\$0.00
Multiple Dependent Claims (check if applicable) _____					\$0.00
TOTAL ADDITIONAL FEE FOR THIS AMENDMENT					\$36.00

- ☐ No additional fee is required for amendment.
☒ Please charge Deposit Account No. 19-1457 in the amount of \$36.00.
 A duplicate copy of this sheet is enclosed.
 A check in the amount of _____ to cover the filing fee is enclosed.
☒ The Commissioner is hereby authorized to charge payment of the following fees associated with this communication or credit any overpayment to Deposit Account No. 19-1457.
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☒ Any additional fees required under 37 C.F.R. 1.16.
☒ Any patent application processing fees under 37 C.F.R. 1.17.


 David C. Ripma, Reg. No. 27,672

 Dated: **SEPTEMBER 19, 2002**

I hereby certify that this correspondence is being facsimile transmitted to the United States Patent and Trademark Office under 37 C.F.R. §1.8 at Fax No. (703) 872-9318 on July 30, 2002.


 David C. Ripma, Reg. No. 27,672

Note: Each paper must have its own certificate or transmission, or this certificate must identify each submitted paper. The papers submitted include:

- | | |
|--|------------|
| <input checked="" type="checkbox"/> This Amendment Transmittal Letter (Duplicate Attached) | 2 page(s) |
| <input checked="" type="checkbox"/> Response under 37 CFR § 1.111 | 23 page(s) |
| <input checked="" type="checkbox"/> Attachments | 0 page(s) |
| <input type="checkbox"/> Petition for Extension of Time under 37 C.F.R. § 1.136 (Duplicate Attached) | page |

Total pages, including this Transmittal: 25

#7/B
9-24-2
Robert
A FinalIN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re Application of:

Inventors: Apostolos Voutsas

Serial No.: 09/893,866

Filed: June 28, 2001

Title: METHOD FOR FORMING
SILICON FILMS WITH TRACE
IMPURITIES) ATTORNEY FILE NO.
) SLA592Do not
enter
AUS
9/27/02CERTIFICATION UNDER 37 CFR § 1.8

I hereby certify that the documents referred to as enclosed herein are being deposited with the United States Postal Service as first class mail on this date 9/19/02, in an envelope addressed to: Assistant Commissioner for Patents, Washington, D.C. 20231.

Date

Signature

David E. Ripma
Reg. No. 27,872BOX RESPONSESAssistant Commissioner for Patents
Washington, D.C. 2023109/25/2002 JROBERTS 00000001 191457 09092006
01 FC:103 36.00 CHAMENDMENT AND REQUEST FOR RECONSIDERATION

In response to a Final Office Action filed July 31, 2002, please accept the following amendments and reconsider.

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SEP 19 2002

IN THE CLAIMS:

TECHNOLOGY CENTER 2800

Please amend claims 6, 9, 19, and 22 as follows.

1. (Unchanged) In the fabrication of liquid crystal displays (LCDs), a method for forming silicon films with a controlled amount of trace impurities, the method comprising:

forming a target including silicon and a first concentration of a first impurity;

supplying a substrate; and